

NEGATIVE RESIST COMPOSITION

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Inventor: FUJIMORI TORU
Applicant: FUJI PHOTO FILM CO LTD
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Abstract of JP2003262959

PROBLEM TO BE SOLVED: To provide a negative resist composition in which occurrence of development defects is significantly decreased.

SOLUTION: The negative resist composition is characterized in that it contains (A) a compound which generates an acid by irradiation of active rays or active radiation, (B) an alkali-soluble resin, (C) a crosslinking agent which crosslinks by an acid, and (D) a fluoro-aliphatic group-containing polymer having a specified repeating unit.

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